

IN THE CLAIMS:

This listing of claims will replace all prior versions, and listings, of claims in the application:

1-29 (Canceled).

30 (Currently Amended). An apparatus for forming thin film on each of a plurality of substrate to make photo-mask blanks, comprising:

a sputtering chamber for carrying out sputtering to form the thin film on a surface of each substrate in a sputtering time, comprising therein:

a single sputtering target ~~therein for carrying out sputtering to form the thin film on a surface of each substrate in a sputtering time,~~

a target holder, and

a substrate holder capable of holding a substrate in a horizontal state, having a rotation mechanism and being rotatable around its center axis, wherein the number of rotations of the substrate is controlled to be an integer during the film formation,

said substrate holder and said target holder being placed so that the target is held opposite to the substrate and a center axis of the target deviates from a center axis of the substrate;

a first load lock mechanism for introducing the substrate into the sputtering chamber and a second load lock mechanism for discharging the substrate with a film formed thereon in the sputtering chamber, each of said first load lock mechanism and the second load lock mechanism comprising a load lock chamber, and

a conveyer for conveying each of the plurality of substrates one by one for introducing each of the substrates into the sputtering chamber,

wherein said conveyer is capable of conveying one substrate at a time to introduce the substrate in the sputtering chamber so that the sputtering time for carrying out the sputtering for a substrate and an interval time which runs from an end of sputtering for one substrate to a start of sputtering for a next substrate are respectively made constant, and

wherein the load lock chamber is capable of accepting one substrate at one time, so that introducing each substrate into and discharging each substrate from the sputtering chamber can be continuously made at a constant interval.

31 (Previously presented). The apparatus of Claim 30 wherein the first load lock mechanism is capable of keeping a substrate subject to the film forming standby until a substrate with film formed thereon by a previous film forming is transferred to the second load lock mechanism.

32 (Previously presented). The apparatus of Claim 31 wherein said load lock mechanism is capable of venting for making the inside room of the load lock chamber into atmospheric pressure for transferring the substrate with outside, evacuating the inside room of the load lock chamber up to a predetermined degree of vacuum for transferring the substrate with the sputtering chamber.

33 (Canceled).

34 (Currently Amended). The apparatus of Claim ~~[[33]]~~ 30 wherein the substrate holder and the target holder are placed so that a surface of the substrate on which the film is formed and a surface of the target forms a predetermined angle.

35 (Previously Presented). The apparatus of Claim 34 wherein the predetermined angle is 10 to 30 degree.

36 (Previously Presented). The apparatus of Claim 34 wherein the predetermined angle is 10 to 15 degree.

37 (Canceled).

38 (Currently Amended). The apparatus of Claim ~~[[37]]~~ 30 wherein ~~the substrate holder is rotatable around its center axis, and~~ the film formation is controlled by detecting a rotation angle of the substrate from the start to the end of the film forming so that the number of rotations of the substrate during the film formation is an integer.

39 (Currently Amended). The apparatus of Claim ~~[[37]]~~ 30 wherein a position of the substrate at the start of film forming is detected by a sensor, and, when the same position is detected by the sensor after an integer times of rotation of the substrate, the film forming is stopped.

40-43 (Canceled).